

Measurement results of DIPIX pixel sensor developed in SOI technology

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1 Introduction

- Silicon-on-insulator Technology
- DIPIX pixel sensor

2 Study of Pixel Behaviour

- Long time stability test

3 Laser Measurements

- Halo Effect
- Optimization of Back Voltage and Integration time

4 Measurements with Americium source

- Data Cleaning
- Signal Clusters and Energy plots
- Comparison of ENC and SNR for CZ-n and FZ-n

5 Conclusions



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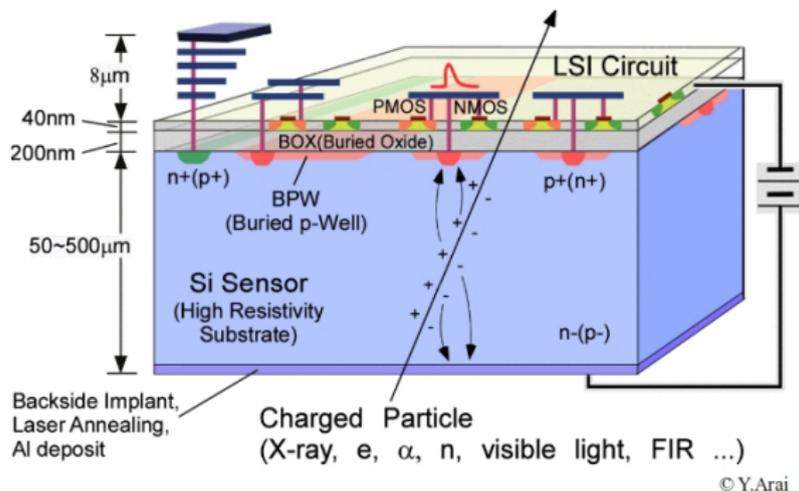
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Silicon-on-insulator Technology

- SOI technology separates devices from the substrate using insulator buried oxide (BOX) layer.
- The features of SOI technology are: high speed, low power, good radiation hardness.
- Back gate effect is mitigated by implanting buried P-well (BPW) just below BOX layer.



Lapis 0.2 μm FD-SOI process

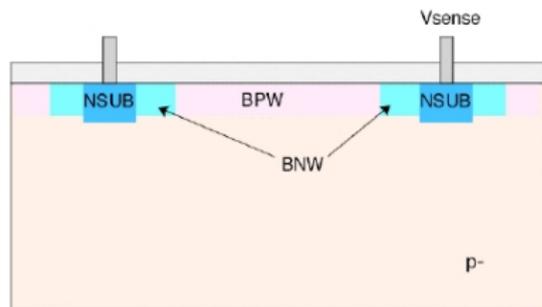
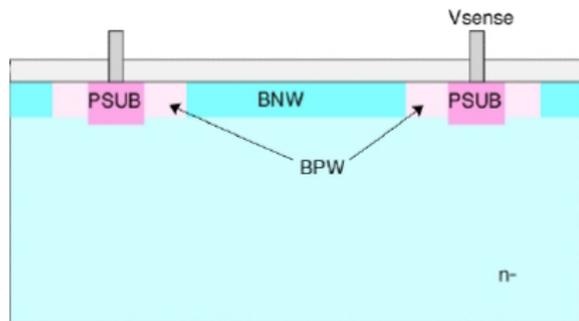
Process	Lapis 0.2 μm FD-SOI CMOS process, 1 Poly, 5 Metal. MIM Capacitor ($1.5 \text{ fF}/\mu\text{m}^2$), DMOS-Cap
SOI wafer	Diameter: 200 mm ϕ , 720 μm thick Top Si : Cz, $\sim 18 \Omega\text{-cm}$, $\sim 40 \text{ nm}$ thick Buried Oxide : 200 nm thick Handle wafer: 1. Cz-n: $\sim 700 \Omega\text{-cm}$ 2. FZ-n: $\sim 7\text{k}\Omega\text{-cm}$
Backside Process	Thinned to 260 μm and Plated with Al (200 nm).



DIPIX pixel sensor

- DIPIX is a Dual mode Integration type PIXEL with reduced pixel size of $14 \mu\text{m}$.
- Circuit is designed to work both in n-type and p-type substrate.
- Internal 10-bit Wilkinson type ADC. (not use in this measurements)

	DIPIX1	DIPIX2
Wafers-Resistivity ($k \Omega\text{-cm}$)	CZ-n (0.7)	CZ-n(0.7) and FZ-n (7)
Pixel size (μm) and No. of pixels	14 and 256×256	14 and $128 \times 256 \times 2$
Chip area and Effective area (mm^2)	5×5 and 3.584	5×5 and 3.584
CDS in Pixel	yes	yes



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Long time stability test

Stability test is to check whether the detector is capable of operating in long run measurements.

Test Setup :

Parameters	DIPIX2
Environment	Dark
Signal	No
No. of Frames	60000
Integration Time	500 μ s
Scan Time (pixel readout time)	640 ns/pixel
RST time without cds and with cds	2040 ns and 2160 ns
RSTV for N-type wafer	750mV and 1300mV

- The Back voltage for CZ-n = 100 V.



Stability Test of CZ-n pixel sensor

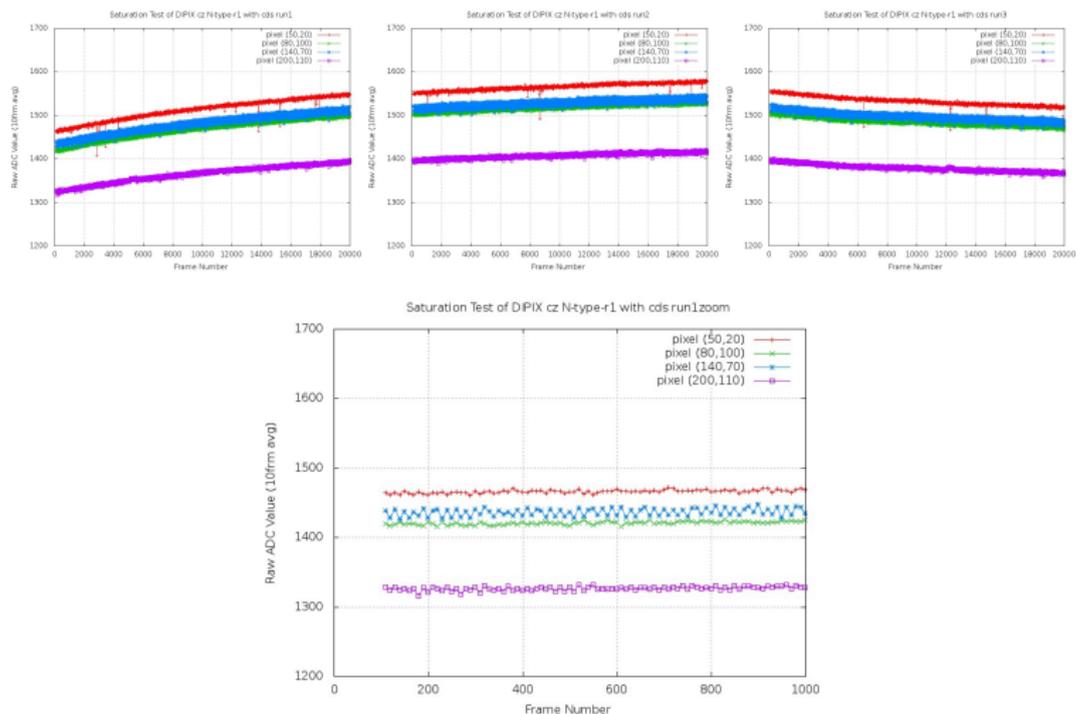


Figure: Stability test of CZ-n with CDS. (top 3 graphs each with 20000 frames measured subsequently and bottom is zoom of initial 1000 frames)



Summary

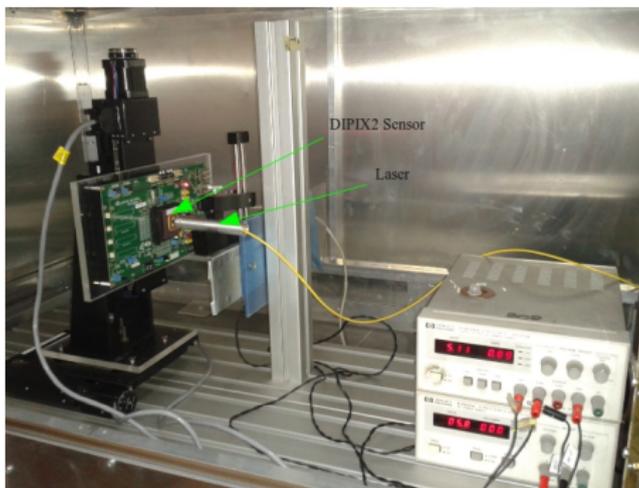
- **DIPIX is stable** and so it may work for long time run.
- Small initial changes in number of counts may probably be reduced by maintaining a constant temperature.



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Laser Details	
Laser Driver	PDL 800-D
Frequency	80 MHz
Modes of operation	Pulse
Laser Head wavelength	1060 nm
3D setup	X,Y and Z



Halo in FZ-n pixel sensor

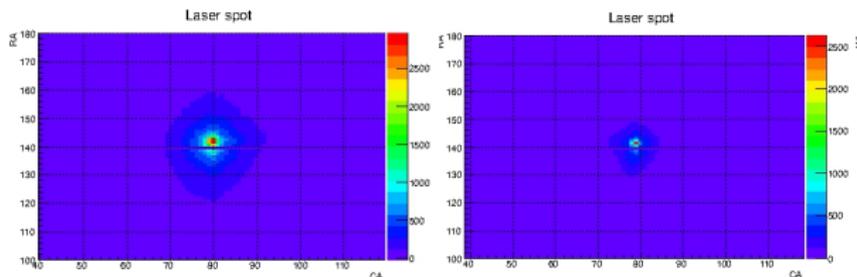


Figure: Back voltage was set to a) Left fig. 10V, b) Right fig. 70V

Halo Effect

- A bunch of pixels around the hit pixel(halo) having 12 to 15 % of hit pixel count is seen.
- This problem is seen in both sensors. The worse is FZ-n.
- Halo depends mostly on Laser Intensity (increase with intensity).

Parameters	CZ-n Type	FZ-n Type
Back Voltage	80V	60V
Integration Time	100 μ s	100 μ s

Table: Optimized Back Voltage and Integration Time

Optimization

- The presence of Halo, force us to do the scan of back voltage and Integration time to optimize them in order to reduce halo.
- Optimization is used to reduce the Halo and spot size.



FZ-n before and after optimization

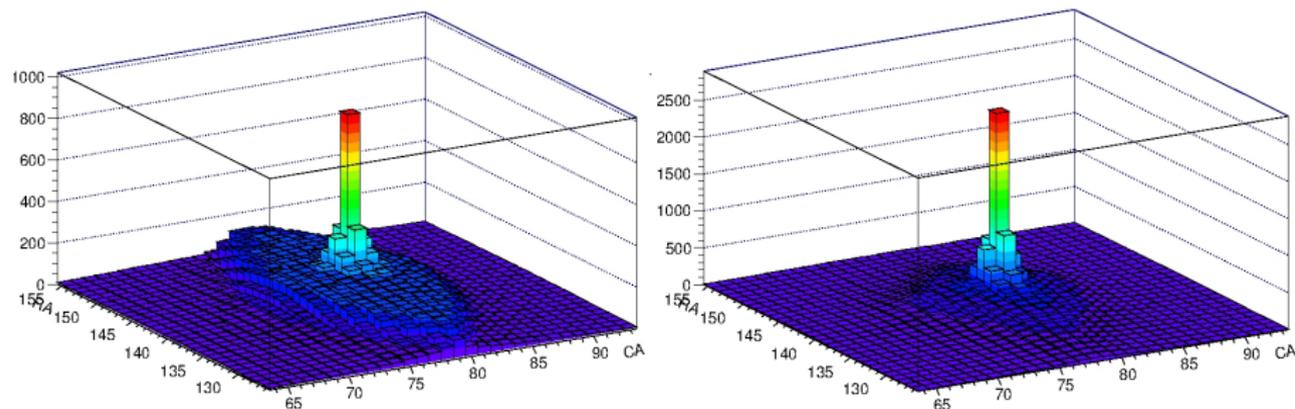


Figure: a) Left fig. Before optimization , b)Right fig. After optimization

Summary

- Halo is seen in both sensors and depends mostly on Intensity. Probably Halo is caused by large charge generation disturbing the electric field.
- Optimized Back voltage and Integration time result in smaller spot size.



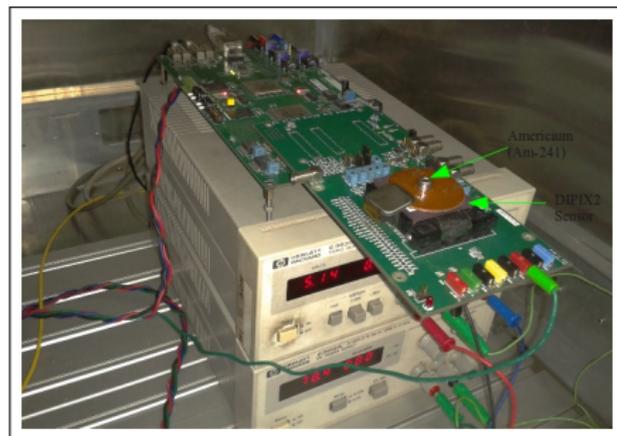
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Americium Radiation Data and Setup

- Am-241 source is used with the activity of 10mCi(=370MBq).
- The rate of incident photons is low.
- Setup is placed in black box.

Radiation Data	
Type	Energy
Gamma	59.5KeV
Gamma	26.3KeV
Gamma	13.9KeV
Cu L x-ray	8.01KeV
Np L-x-ray	17.7KeV
Np L-x-ray	20.7KeV



Data Cleaning using CZ-n pixel sensor

Integration Time and Scan Time	100 μ s, 640 ns/pixel
Back Voltage	80 V
RSTV and RST time	750 mV, 2040 ns
Run Mode	calib data and signal data
Calib run (dark, no source)	500 events
Am-241 run (dark)	20000 events

Table: Parameter setting of sensor CZ-n Type

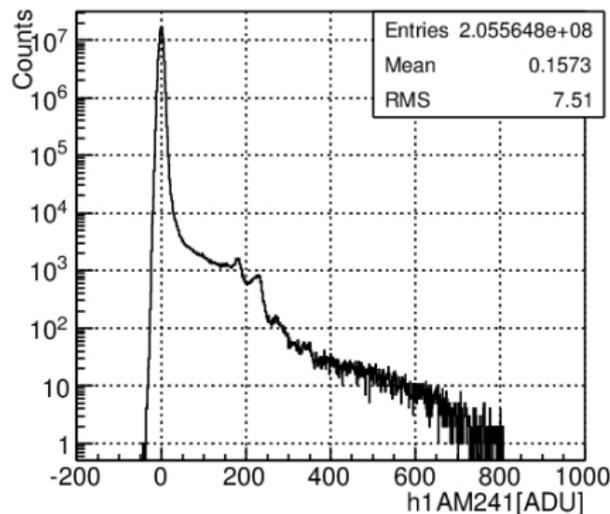
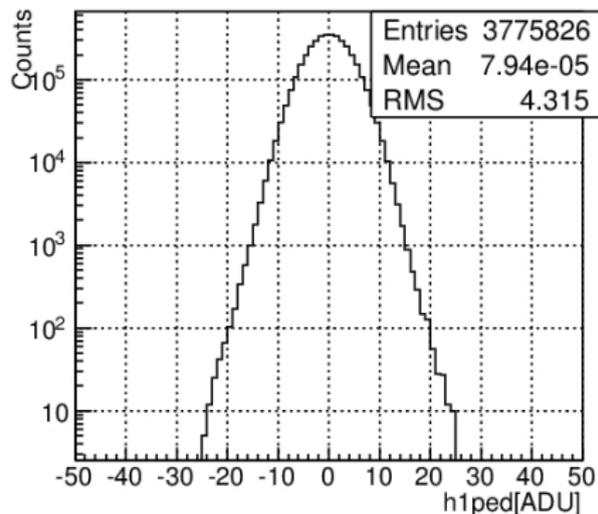
Noise cleaning

- Calib data is used to remove bad pixels.
- Bad frames and common mode noise are removed from both calib and Am-241 run.



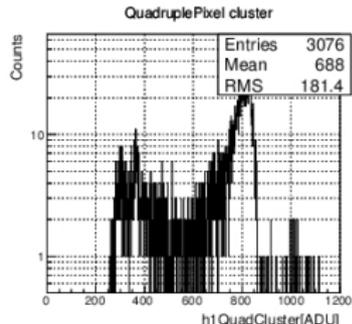
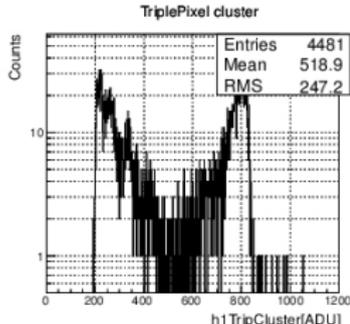
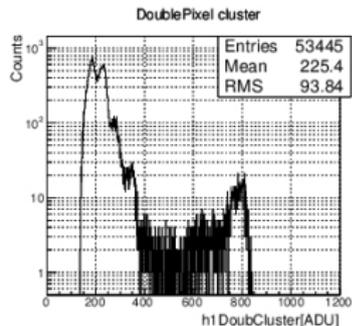
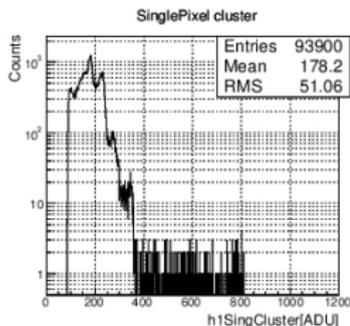
Data Cleaning

- Sensor = CZ-n, CDS = off, No. of frames = 20000 Am-241 and 500 calib runs.
- Back voltage = 80 V, IT = 100 μ s, Pixel scan time = 640 ns.

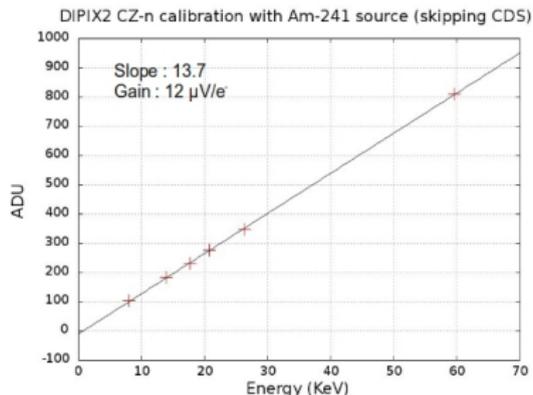
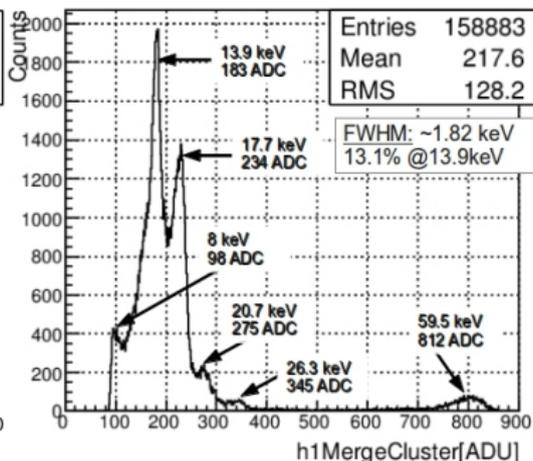
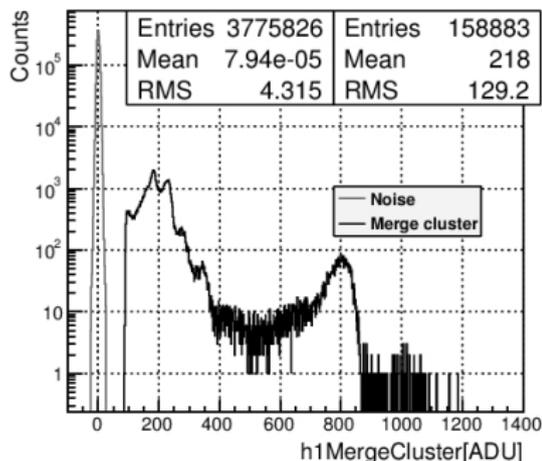


Clustering

- Number of pixels in a cluster depends on deposited energy.
- Total 4σ threshold is used to get hit pixels and these pixels are used to find the cluster.



CZ-n sensor signal Clusters and Energy plots



ENC and SNR Results

CZ N-Type Without CDS					
Region	IT(μ s)	Noise (ADC)	ENC(e^-)	SNR	59.5KeV (ADC)
1	100	4.3	$\simeq 86$	$\simeq 189$	812
CZ N-Type With CDS					
Region	IT	Noise	ENC(e^-)	SNR	59.5KeV (ADC)
1	100	3.6	$\simeq 85$	$\simeq 192$	690

FZ N-Type Without CDS					
Region	IT(μ s)	Noise (ADC)	ENC(e^-)	SNR	59.5KeV (ADC)
1	100	5.1	$\simeq 127$	$\simeq 129$	657
2	100	4.7	$\simeq 141$	$\simeq 115$	543

Summary

- 1st region is the best of both sensor (ENC=85 e^- and SNR=189 using Am-241 source 59.6keV), 2nd region is having lot of bad and hot pixels.
- Readout with CDS give similar results.

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Conclusions

- DIPIX2 shows long time stable operation.
- Halo problem seen with laser can be reduced using small intensity and optimized back voltage. Halo is not seen with americium source.
- CZ-n is having good SNR and ENC ($85e^-$), whereas FZ-n is worse ($ENC = \simeq 127e^-$).
- More study is needed to understand the CDS readout.



Thank you for your attention!



Backup: Stability Test of FZ-n

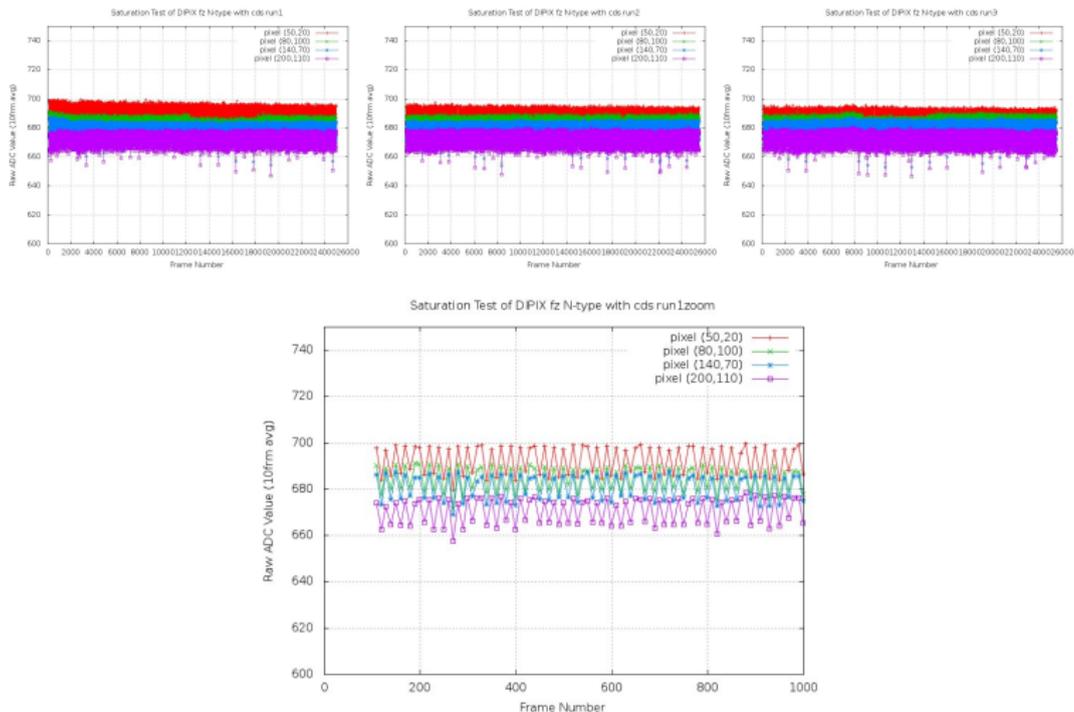


Figure: Stability test of FZ-n with CDS. (top 3 graphs each with 20000 frames measured subsequently and bottom is zoom of initial 1000 frames)



Backup: CZ-n before and after optimization

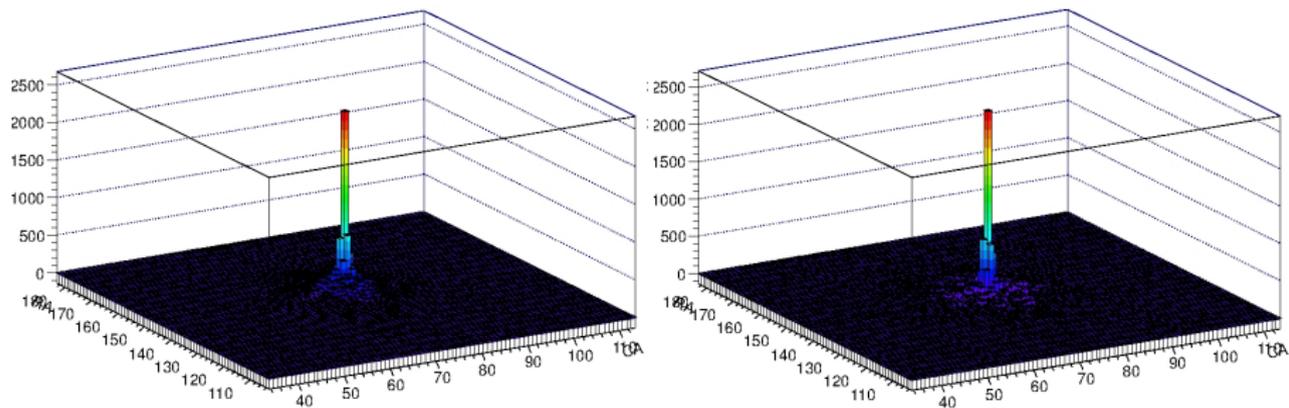


Figure: a) Left fig. Before optimization , b)Right fig. After optimization

